

# Resource Summary Report

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## JEOL: JBX-9500FS Electron Beam Lithography System

RRID:SCR\_020171

Type: Tool

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### Proper Citation

JEOL: JBX-9500FS Electron Beam Lithography System (RRID:SCR\_020171)

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### Resource Information

**URL:** <https://www.jeolusa.com/PRODUCTS/Photomask-Direct-Write-Lithography/Electron-Beam-Lithography/JBX-9500FS>

**Proper Citation:** JEOL: JBX-9500FS Electron Beam Lithography System (RRID:SCR\_020171)

**Description:** Electron beam lithography system that is versatile in its applications from basic research of elements to test production of optical elements to research and development for masks for high accelerating voltage exposure.

**Resource Type:** instrument resource

**Keywords:** Jeol, JEOL, Electron Beam Lithography System, Instrument Equipment, USEDit,

**Availability:** Commercially available

**Resource Name:** JEOL: JBX-9500FS Electron Beam Lithography System

**Resource ID:** SCR\_020171

**Alternate IDs:** Model\_Number\_JBX\_9500FS

**Record Creation Time:** 20220129T080349+0000

**Record Last Update:** 20260912T195930+0000

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### Ratings and Alerts

No rating or validation information has been found for JEOL: JBX-9500FS Electron Beam Lithography System.

No alerts have been found for JEOL: JBX-9500FS Electron Beam Lithography System.

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## Data and Source Information

**Source:** [SciCrunch Registry](#)

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## Usage and Citation Metrics

We have not found any literature mentions for this resource.